

ABSTRACT OF DISCLOSURE

A method for producing a photoresist master adapted for use in the manufacture of an optical information medium is provided. This method has enabled formation of a fine pattern having a minimum width which is about half of the wavelength used for the exposure, and in this method, decrease in the pattern height has been suppressed and tapering of the pattern profile has been improved. In this method comprising the steps of applying a photoresist layer on a substrate, exposing the photoresist layer to a laser beam to form a latent image in the photoresist layer, and developing the latent image to form a protrusion/depression pattern to thereby produce the photoresist master, and in this method; a light absorbing layer is formed between the substrate and the photoresist layer and in contact with the photoresist layer, and the light absorbing layer exhibits light absorption at the wavelength of said laser beam.